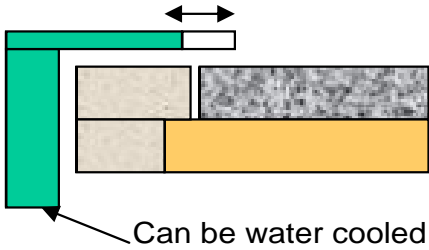
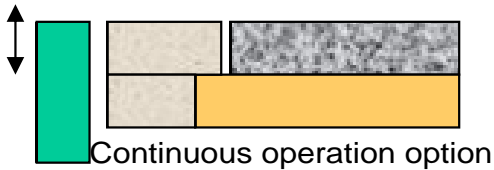
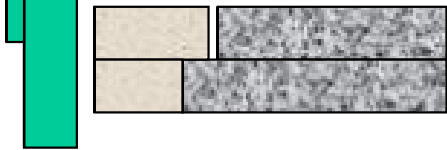


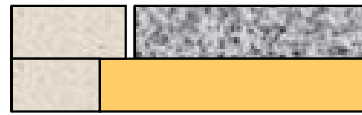
Mechanical Aspects



Long life anode for continuous sputtering of thick targets

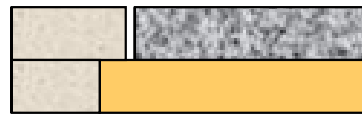


Chamber flange



Lower cost anode option

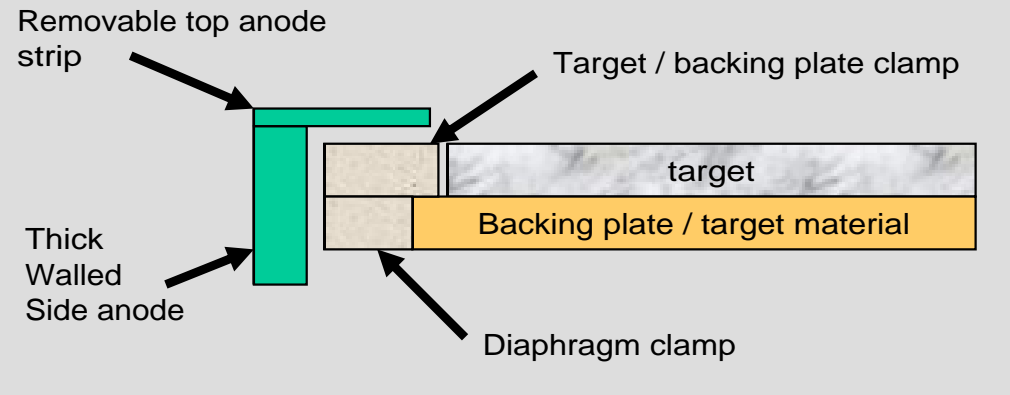
Chamber flange



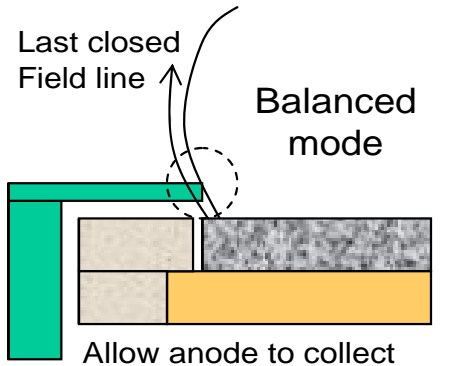
Note: The anode is always an integral part of the magnetic field design and should always be application specific

GENCOA

The Importance of anodes

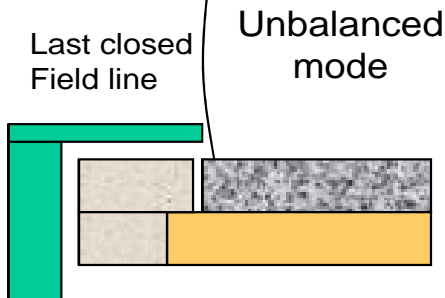


DC sputtering

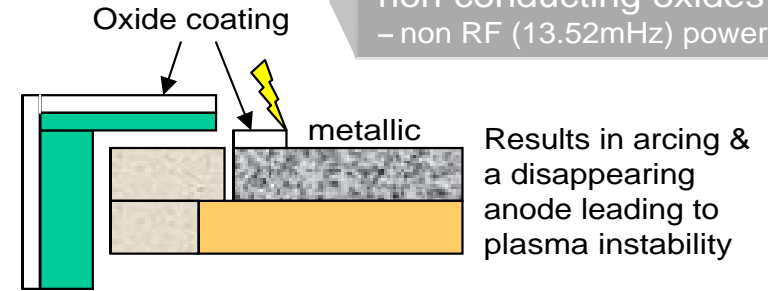


Allow anode to collect electrons before reaching the substrate

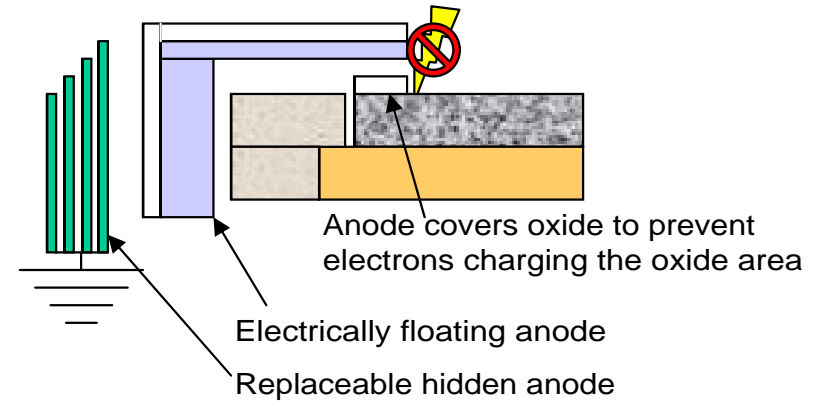
Allow all electrons to escape the magnetron plasma



Reactive sputtering of non-conducting oxides - non RF (13.52MHz) power



Single cathode solution



2nd solution - use 2 magnetrons with AC or MF power; see Gencoa AS magnetrons
 3rd solution - Gencoa's new full face (FFE) erosion magnetrons - no oxide on target

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